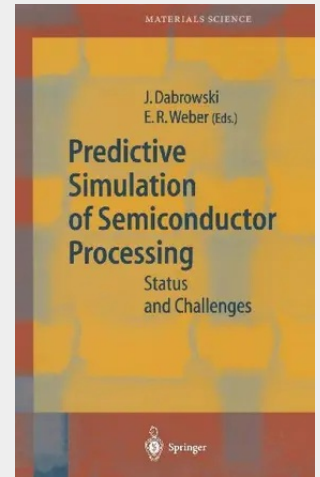


# Predictive Simulation of Semiconductor Processing

Status and Challenges

**Predictive Simulation of Semiconductor Processing** enables researchers and developers to extend the scaling range of semiconductor devices beyond the parameter range of empirical research. It requires a thorough understanding of the basic mechanisms employed in device fabrication, such as diffusion, ion implantation, epitaxy, defect formation and annealing, and contamination. This book presents an in-depth discussion of our current understanding of key processes and identifies areas that require further work in order to achieve the goal of a comprehensive, predictive process simulation tool.

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**235,39 €**

219,99 € (zzgl. MwSt.)

*Lieferfrist: bis zu 10 Tage*

**Artikelnummer:** 9783540204817  
**Medium:** Buch  
**ISBN:** 978-3-540-20481-7  
**Verlag:** Springer  
**Erscheinungstermin:** 05.05.2004  
**Sprache(n):** Englisch  
**Auflage:** 2004  
**Serie:** Springer Series in Materials Science  
**Produktform:** Gebunden  
**Gewicht:** 1028 g  
**Seiten:** 490  
**Format (B x H):** 160 x 241 mm

